

Abstract

An integrated etch/strip/clean apparatus is disclosed. The apparatus includes an etching line to etch and clean a substrate, a stripping line to strip the etched substrate, and a cleaning line to clean and dry the substrate. The cleaning line is on the stripping line. Accordingly, etch, strip and cleaning processes is performed by a single equipment. As a result, processing time installation space requirement of the equipment are reduced. Further, contamination of the substrate is prevented.